

Sample question paper in MCQ format

- 1 Removing the exposed photoresists process is known as _____
a. developing b. lift-off c. stripping d. cut-off
- 2 One of the standard substrate cleaning procedure is _____
a. RCA cleaning b. CRA cleaning c. wafer cleaning d. water cleaning
- 3 In optical lithography patterns are transferred on the template using _____
a. pattern generator b. stencil c. optical mask d. photon generator
- 4 Mask aligner is the equipment used for _____
a. depositing films b. spinning photoresist c. pattern transfer d. developing photoresist
- 5 Use of X-rays in lithography is commonly known as _____
a. UV lithography b. extreme UV lithography c. normal lithography d. IR lithography
- 6 The mask having dark features and transparent background is _____
a. dark field mask b. bright mask c. gray mask d. black and white mask
- 7 Gray mask is specially designed to pattern the _____
a. 1D objects b. 0D objects c. 2D objects d. 3D objects
- 8 To deposit insulating layer of SiO₂ on the template following deposition technique is recommended _____
a. Thermal evaporation b. e-beam evaporation c. chemical vapor deposition d. chemical bath deposition
- 9 Thickness of a human hair is _____
a. 100 nm b. 200 nm c. 100 micron d. 200 micron
- 10 In the case of SWCNT-FETs the SWCNTs used works as _____
a. scarifying material b. active material c. insulating material d. contact material